## **R&D of Commercially Produced Large GEM Foils**

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#### Matt Posik, Xuan Li and Bernd Surrow

for the STAR Collaboration Temple University, College of Science and Technology, Philadelphia, PA





#### **Motivation**

- Currently CERN is the only main distributor of GEM foils. Many future detectors are being designed with GEM foil technology in mind. This escalates the need for commercially available GEM foils.
- GEM foils are well suited for high energy particle detectors.
- Recent tracking upgrade of STAR experiment took advantage of large double-mask GEM foils (~ 30 cm x 30) cm) to achieve electron/positron charge separation.
- $\blacksquare$  EIC will require even larger GEM foils (  $\ge$  50 cm x 50 cm).
- It is not practical to produce larger GEM foils via the double-mask process. Therefore, a single-mask process has been established.

### **Single-Mask GEM Foil Production**

- The single-mask GEM fabrication employs a glass mask for the photolithographic process. The chemical etching is based on a single-sided etching process.
- The advantage of using the single-mask process is that it removes the need to align two masks, as is done in the double-mask process, which allows for much larger foils.
- Tech-Etch has now established a single-mask process, and has produced 10 cm x 10 cm and 30 cm x 30
- cm GEM foils.

Drift

GEM

GEM

PCB

Readout

100

0.009755

0.03884

Cathode





#### **Double-Mask GEM Foil Performance**



The GEM foil holes were etched using a double-mask photolithographic technique performed by Tech-Etch. In this process the holes were chemically etched on both sides of the foil, and each mask was aligned so the holes matched up. Double-mask GEM foil technology has already been successfully used in the STAR Run 13 experiment via the

Electronics



- The gain achieved from a GEM foil and its uniformity depends on the foil's geometric properties and its hole uniformity.
- The pitch, inner and outer hole diameters, and hole uniformity of the 10 cm x 10 cm Tech-Etch singlemask GEM foils were measured using an optical scanning setup at Temple University.
- The mean optical properties reflect the desired parameters and are consistent with those found in doublemask GEM foils.
- **General Second Second**
- The electrical properties of both the single-mask 10 cm x 10 cm and FGT sized foils performed very well. Current leakages, performed in a nitrogen environment, were typically measured to be < 1 nA for voltages < 600 V. These results are superior to that of the double-mask GEM foils due to the replacement of Kapton







• Tracking residuals of ~ 200  $\mu$ m in the R plane and ~ 1 mrad in the  $\varphi$  plane lead to a detector resolution of ~150 µm.

**a** A charge separation (without the use of TCP tracking) of ~ 2.5  $\sigma$  was achieved.



#### FGT: quad 1A, plane=Phi, strip=720



**Spacer + Mylar foil** Disk setup used to hold 12 triple GEM segments **Triple GEM Detectors** Summary The FGT performed well in Run 13, providing good tracking residuals, allowing for a clear charge separation at forward rapidity without using the TPC inner/outer pad planes. Electrical and geometrical quality assurance (QA) analysis has been completed for the Tech-Etch produced 10 cm x 10 cm single-masked GEM foils. Electrical QA has been completed for the Tech-Etch produced FGT sized single-masked GEM foils. Geometrical QA analysis is currently underway. **Discussions have begun with Tech-Etch to manufacture GEM foils up to about 1 m x 0.5 m.** Initial design work towards an EIC GEM detector is progressing.

AGS-RHIC Users Meeting, BNL, Upton, NY, USA, June 17-20, 2014